

Operation of a Reactive Magnetron Sputtering Ion Source using Water Vapor Plasma

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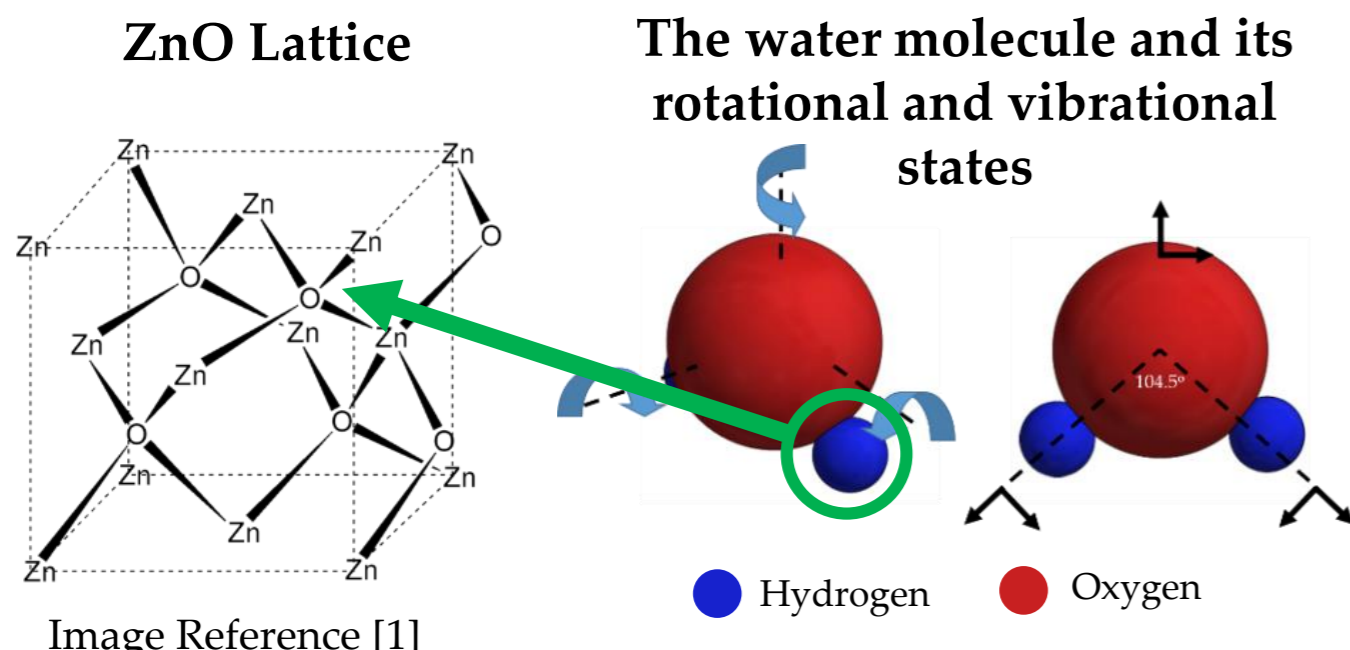


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Water Vapor Plasma

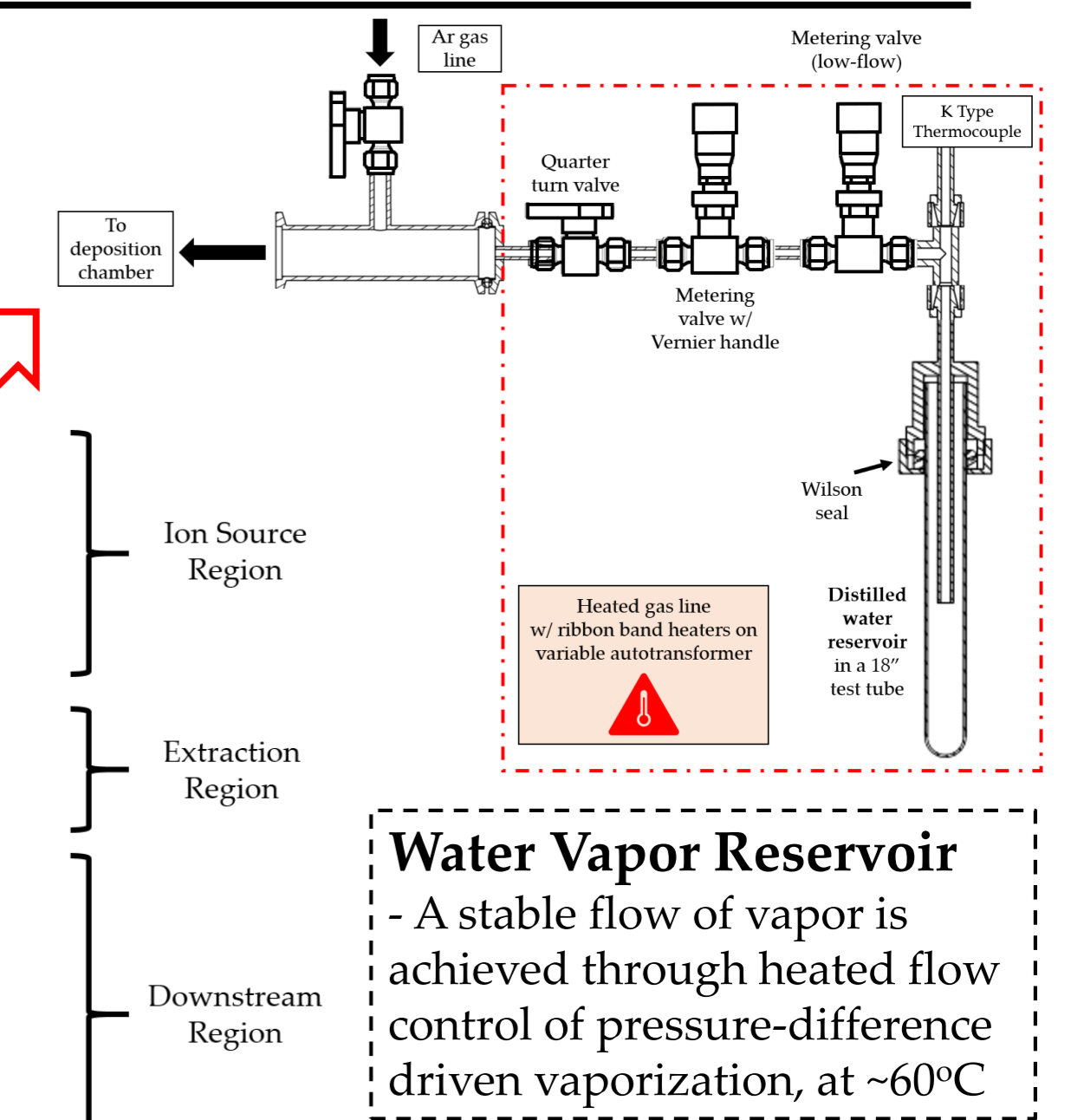
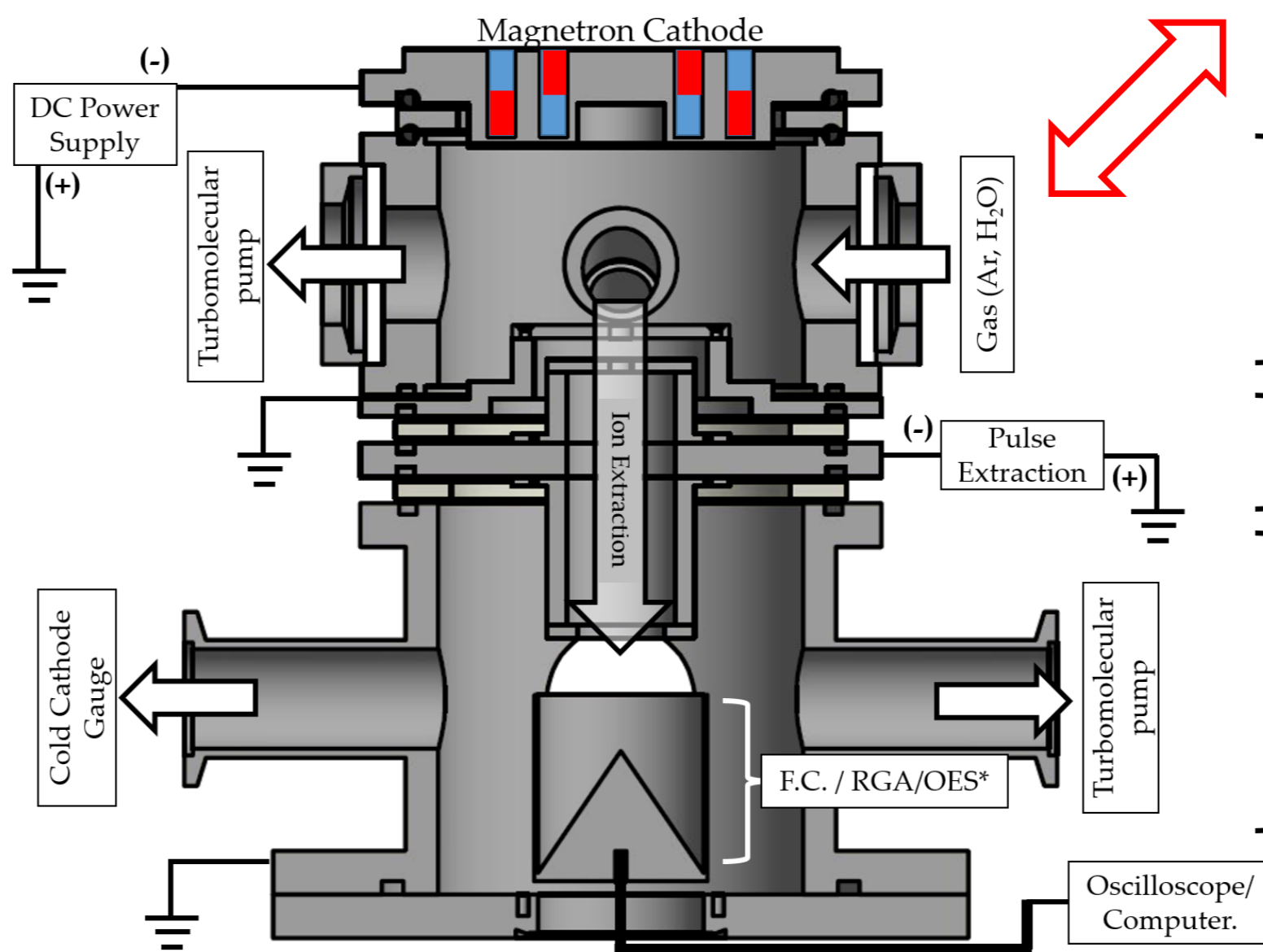
- has widely been used in:
 - Surface modification
 - Functional film deposition of oxides, as a substitute for conventional O₂ gas in TiO₂, In₂O₃, and ZnO.
- By extracting from an ion source, low energy deposition of nanoparticles with minimal damage to sensitive surfaces can be achieved



Effect of H₂O to ZnO:

- Increased conductivity through shallow donor doping.
- Lattice stress relaxation

DC Reactive Magnetron Sputtering Ion Source



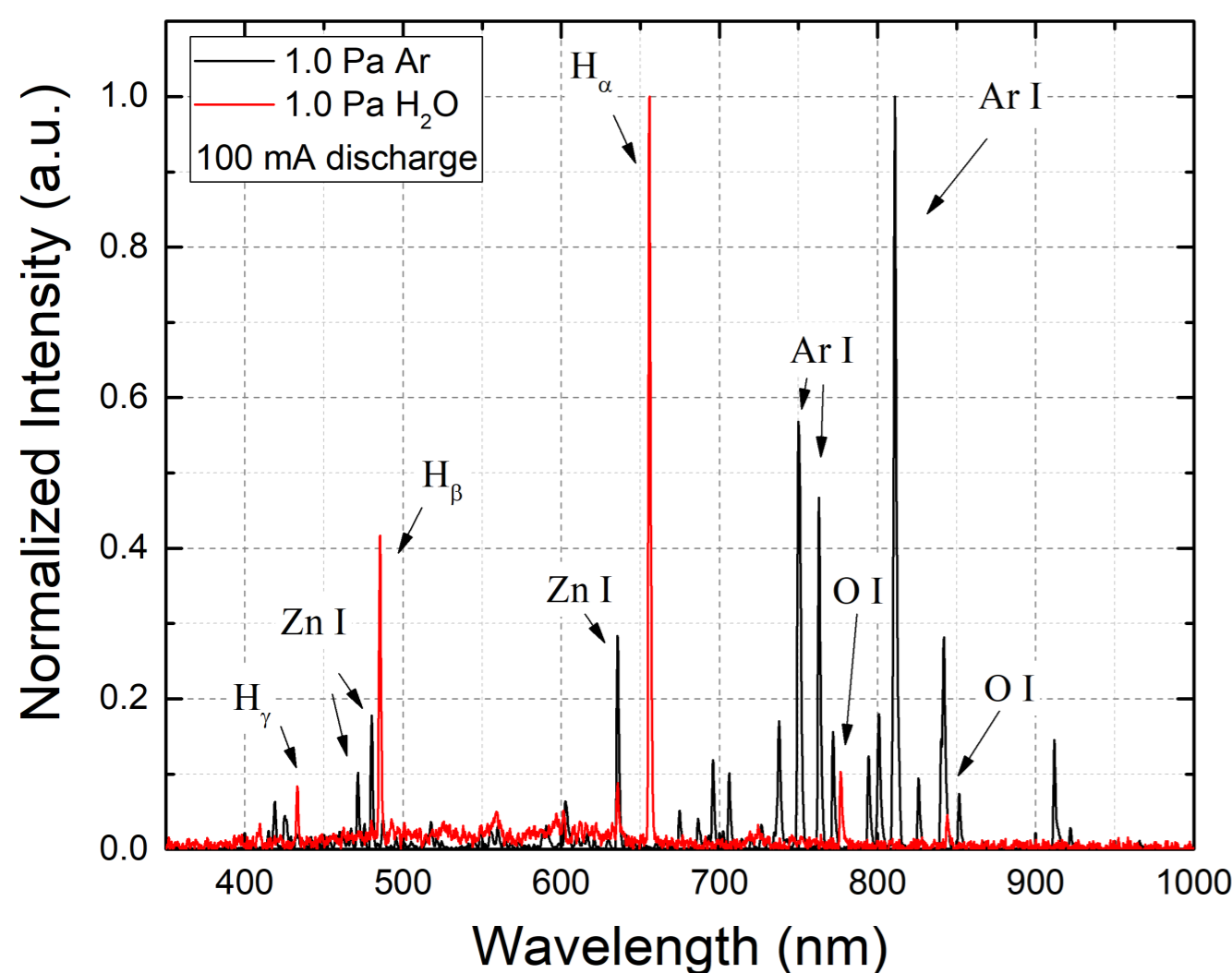
Water Vapor Reservoir

- A stable flow of vapor is achieved through heated flow control of pressure-difference driven vaporization, at ~60°C

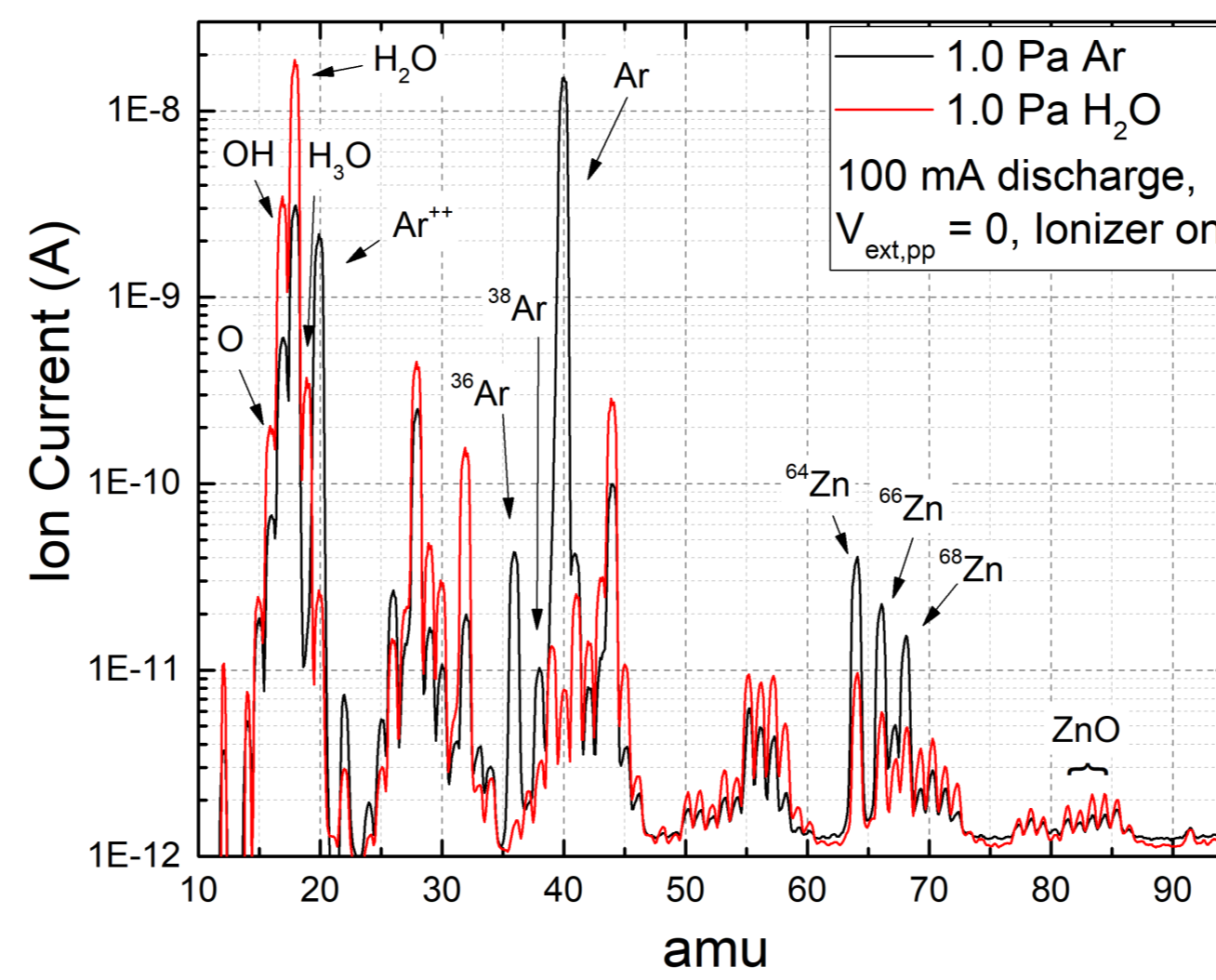
*OES is performed in the same axis, but without the extraction region and differential pumping

- The system utilizes a 70-mm ϕ Zn (99.2%) metal target with a toroidal magnetron configuration
- The extraction region is 40.0 mm away from the target and has a 2.0-mm aperture grounded aperture, spaced 4.8-mm from the extraction conduit, which has a total length of 72.0 mm.
- With a grounded ion source, pulsed extraction is done using a high speed amplifier (NF 4020) with $V_{ext,pp} = -100V$, from 1KHz to 500KHz

Ion Species in a Reactive Magnetron Sputtering Ion Source



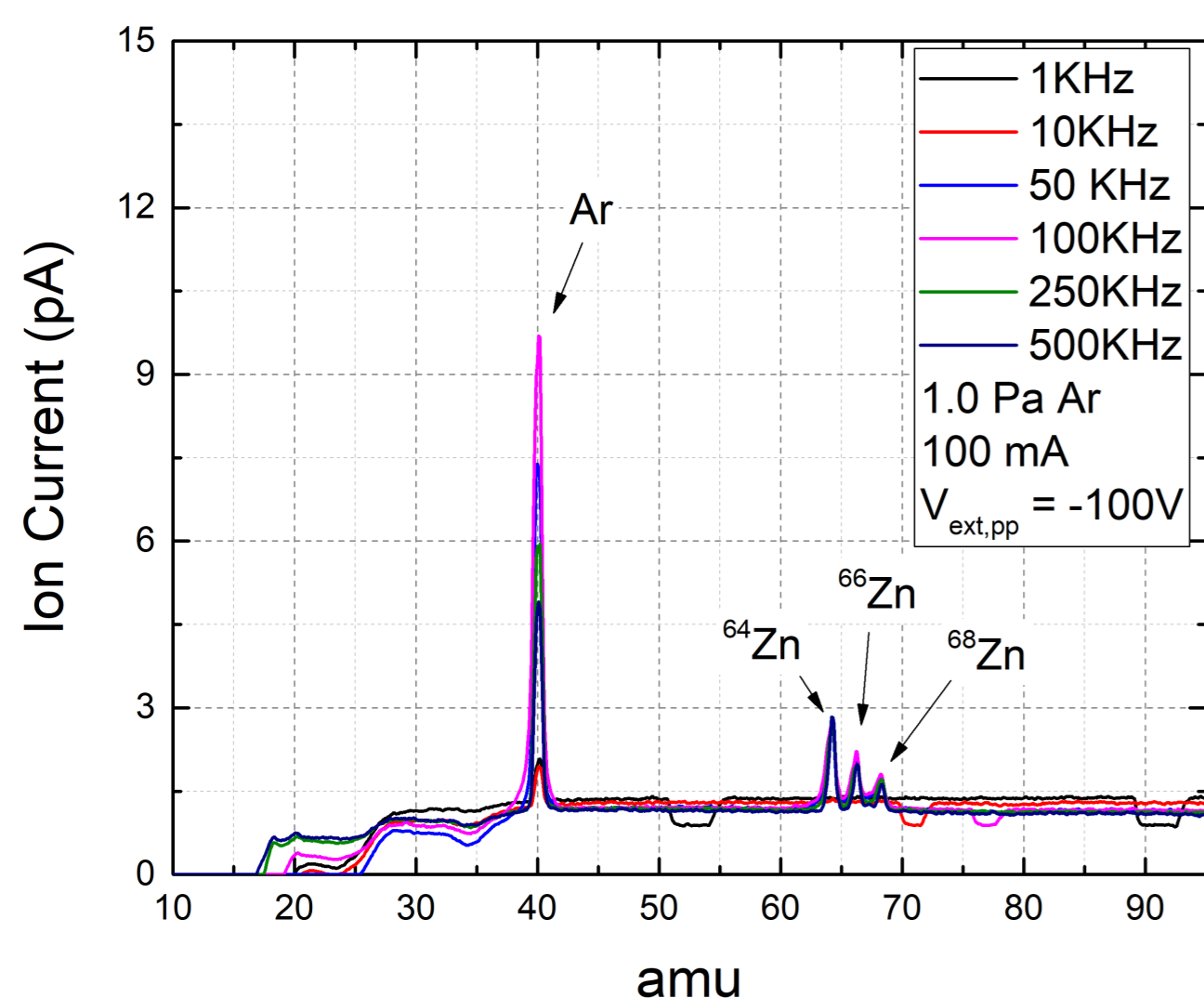
Optical Emission Spectra of Ar and H₂O Plasma



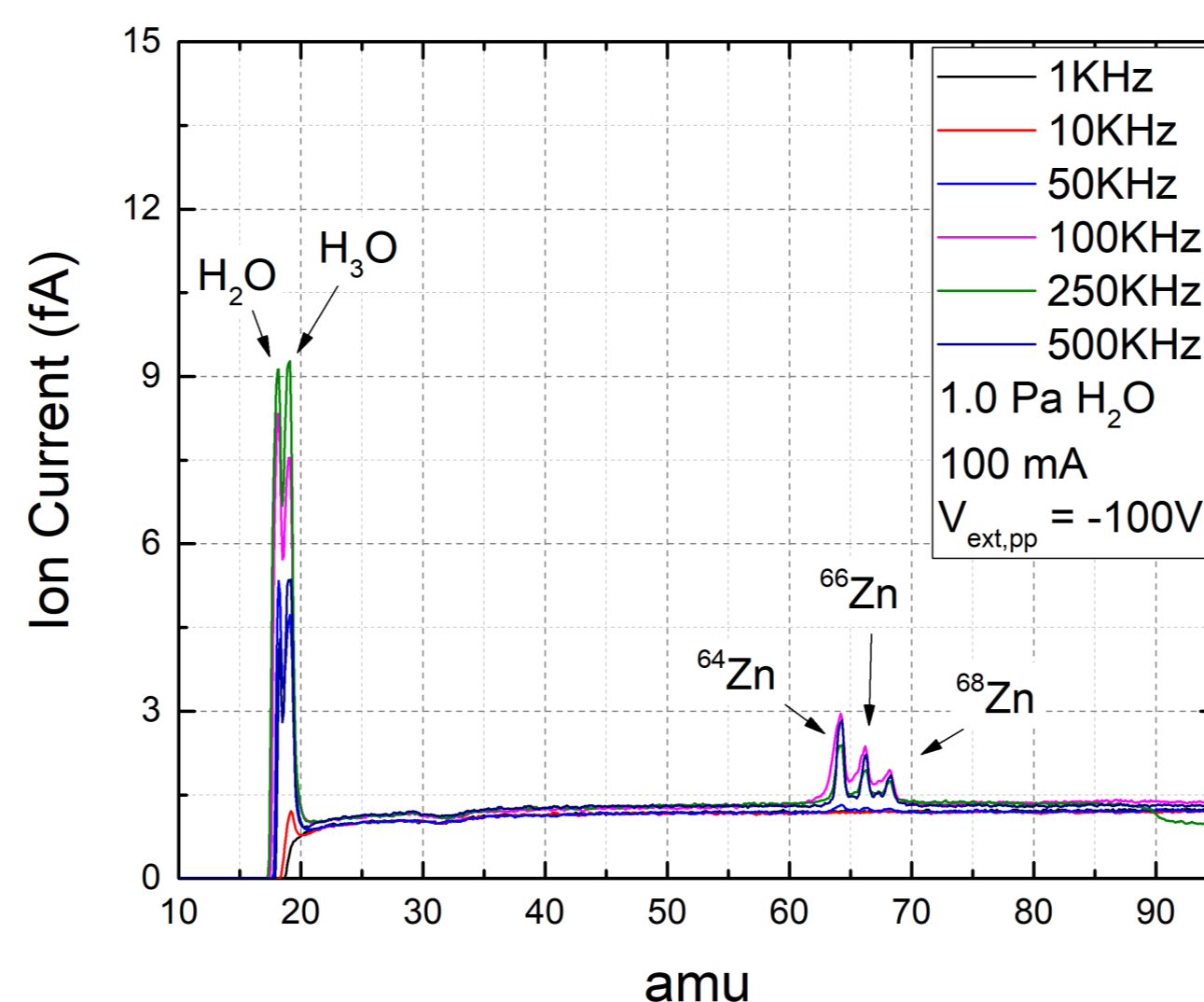
Mass spectra of Ar and H₂O plasma without an extraction potential

- The optical emission spectra was first measured in the ion source to confirm the introduction of water vapor.
- From the spectra, the peak intensity of O I is considerably lower than that of H α and Zn I.
- The mass spectra of the Ar and H₂O plasma were measured using a quadrupole mass analyzer (SRS RGA100) with a filament ionizer in the differentially pumped downstream region, without a pulsed extraction potential
- Zn and ZnO neutrals were transported from the ion source when Ar and H₂O plasma were used.
- For water vapor plasma, the ratio of O I (777nm) to H α is 0.103 while the OH to H₂O intensity is 0.184

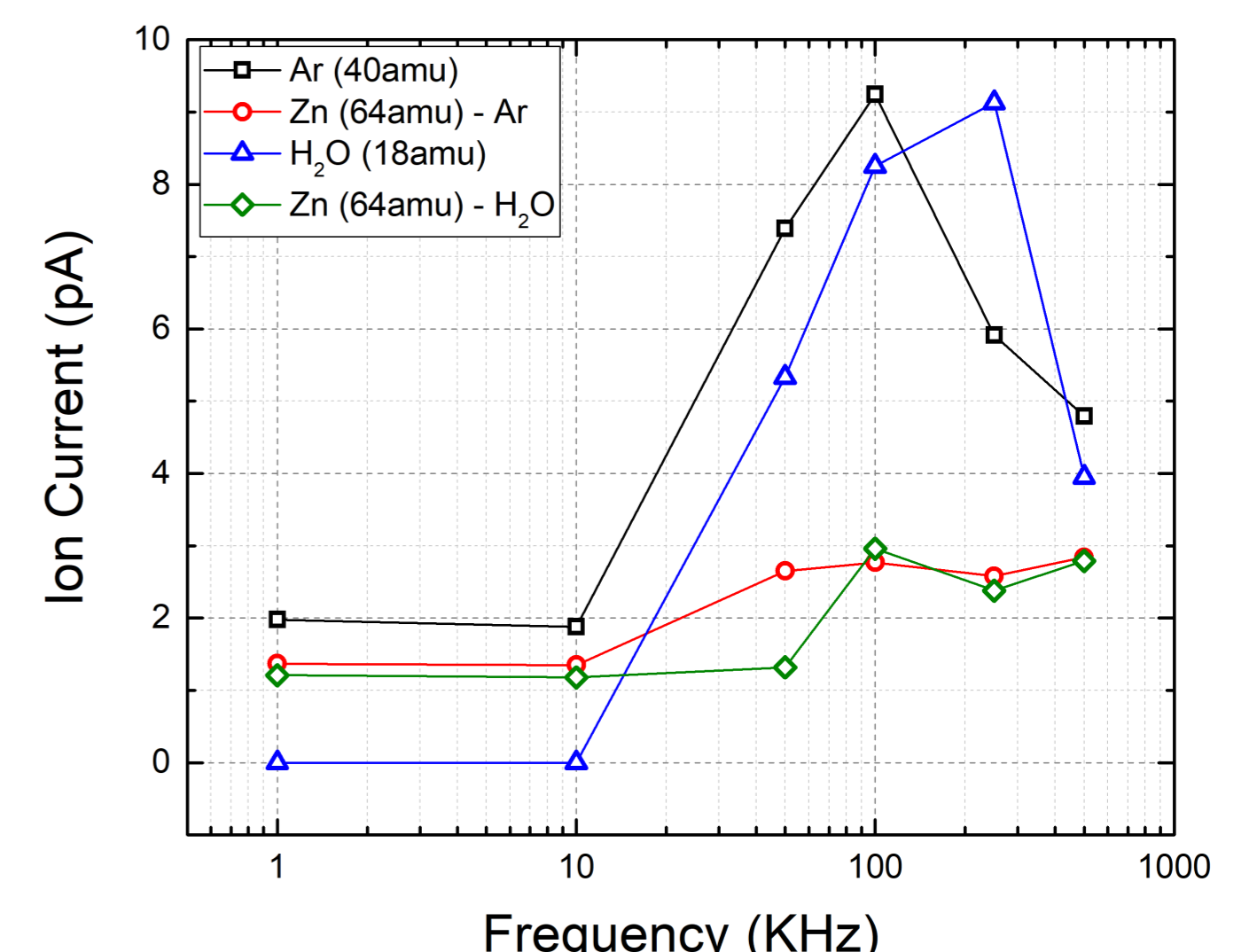
Pulsed Ion Extraction from a DC Reactive Magnetron Sputter Ion Source



Mass spectra of Ar plasma (1.0 Pa)



Mass spectra of H₂O plasma (1.0 Pa)



Variation of ion peak current

- Extraction was measured using the QMA without the filament ionizer, to measure and identify the ion species extracted from the ion source.
- For Ar plasma, the species detected were Ar (40amu) and Zn (64,66,68 amu), while for H₂O plasma, it were H₂O (18amu), H₃O (19amu) and Zn (64,66,68amu). ZnO was not observed in the H₂O plasma.
- The discharge ion peak intensity increased as the extraction frequency increased, with a maximum peak signal observed at 100KHz for Ar and 250KHz for H₂O. After the maximum, a decrease in the intensity was observed
- The Zn ion peaks were only observed at 50KHz and 100KHz for Ar and H₂O plasma, respectively. The ion current did not increase as the frequency was further increased.

Main References:

[1] C.G. Van De Walle: Hydrogen as a cause of doping in zinc oxide, Physical Review Letters, 85 (2000), 1012–1015.

[2] Vasquez, M.R., Iasin, M.D., Pengson, L.T.O., Ramos, M.K., Cuevas, A.G: Extraction and transport of low-energy Ar ion beams with a broad cross-section, Vacuum 187 (2021), 1-7

[3] Kawamura, Y., Hattori, N., Miyatake, N., Uraoka, Y.: Comparison between ZnO films grown by plasma-assisted atomic layer deposition using H₂O plasma and O₂ plasma as oxidant

[Image Reference 1] Image taken from: <https://www.acs.org/content/acs/en/molecule-of-the-week/archive/z/zinc-oxide.html>